Amendments to the Specification

Please replace the paragraph beginning on page 21, line 2, and ending on page 22, line 5, with the following rewritten paragraph:

Accordingly, an autofocus sensor (hereinafter referred to as "AF sensor"), which serves as a multi-point focus position-detecting system based on the optical system and based on the oblique incidence system, is arranged on the side surface of the projection optical system PL. The AF sensor is used to detect the focus position at a plurality of detecting points in the exposure area on the surface of the wafer W and in the pre-reading area disposed in front thereof in the scanning direction. A result of detection is supplied to a focusing control system ~~5445~~. Fig. 1 shows those included in the AF sensor, i.e., an AF sensor 44B for detecting the focus position in the exposure area, and AF sensors 44A, 44C for detecting the focus position in the pre-reading areas in the two directions. The focusing control system 45 calculates the control amount of the angle of inclination and the focus position of the Z tilt stage 9 corresponding to the position of the wafer W in order to focus the surface in the exposure area of the wafer W to the image plane of the projection optical system PL, from the supplied information on the focus position under the control of the main control system 7. The operation of the Z tilt stage 9 is controlled on the basis of the control amount in accordance with the autofocus system and the autoleveling system. In this embodiment, a result of measurement of the pitching amount for the scanning direction of the Z tilt stage 9 is also supplied to the focusing control system 45. The focusing control system 45 corrects the control amount of the angle of inclination and the focus position of the Z tilt stage 9 on the basis of the result of measurement of the pitching amount.